

L Number	Hits	Search Text	DB	Time stamp
5	4	(coat coating deposit depositing deposition film layer layering) near3 (silicon near (carbide nitride oxide dioxide) "si.sub.3.N.sub.4" "si.sub.3 n.sub.4" "sio.sub.2" "si O.sub.2" "SiC" "Si C") and ((438/121,122,for.436).CCLS.) and @pd>=20030204	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/05/21 09:56